

ABSTRACT

EXTREME ULTRAVIOLET LITHOGRAPHY SYSTEM HAVING CHUCK ASSEMBLY AND METHOD OF MANUFACTURING THEREOF

An EUV lithography system and method of manufacturing thereof includes: an EUV light source; a chuck being thermally conducting and smooth having a surface with a predetermined chuck flatness; and a reflective lens system for directing EUV light from the EUV light source over the surface of the chuck.

FIG. 2